

Solution 3.1

With the process parameters follows the $0.13\mu\text{m}$ technology:

a) $V_{T0} = \Phi_{GC} - 2\Phi_F - Q_{B0}/C_{ox} - Q_{ox}/C_{ox}$

NMOS: $V_{T0p} = -0.99\text{V} - (-0.88\text{V}) - (-0.188\text{V}) - 0.06\text{V} = 0.02\text{V}$

PMOS: $V_{T0n} = 0.99\text{V} - (0.88\text{V}) - (0.188\text{V}) - 0.06\text{V} = -0.14\text{V}$

b) $\Phi_{GC} = \Phi_F - \Phi_G(\text{Gate})$

$\Phi_{GC}|_{\text{NMOS(n-gate)}} = \Phi_{Fp} - 0.55, (\phi_{Fp} < 0)$

$\Phi_{GC}|_{\text{PMOS(p-gate)}} = \Phi_{Fn} + 0.55, (\phi_{Fn} > 0)$

$\Phi_{GC}|_{\text{PMOS(n-gate)}} = \Phi_{Fn} - 0.55, (\phi_{Fn} > 0)$

The work function is estimated with the intrinsic Fermi level as a reference point. For the threshold voltage of the PMOS transistor (with p^+ doping) the following results in $V_{T0n} = (-0.11\text{V}) - (0.88\text{V}) - (0.188\text{V}) - 0.06\text{V} = -1.24\text{V}$

c) $N_I = (C_{ox}/q)\Delta V$

NMOS: $N_I = (10^{+13}\text{V}^{-1}\text{cm}^{-2})(0.4\text{V} - (0.02\text{V})) = 3.8 \cdot 10^{12}\text{cm}^{-2}$

PMOS: $N_I = (10^{+13}\text{V}^{-1}\text{cm}^{-2})(-0.4\text{V} - (-0.14\text{V})) = -2.6 \cdot 10^{12}\text{cm}^{-2}$

PMOS: $N_I = (10^{+13}\text{V}^{-1}\text{cm}^{-2})(-0.4\text{V} - (-1.24\text{V})) = 8.4 \cdot 10^{12}\text{cm}^{-2}$

d) $|V_{T0}| < V_{DD}$, $|V_{T0}|$ can't be higher than V_{DD} .

e)

$$\begin{aligned}\mu_e &= \frac{\mu_0}{1 + \left(\frac{V_{GS} - V_T}{\theta \cdot t_{ox}} \right)^\eta} \\ &= \frac{130\text{cm}^2\text{V}^{-1}\text{s}^{-1}}{1 + \left(\frac{0.8\text{V}}{4 \cdot 10^6\text{Vcm}^{-1} \cdot 22 \cdot 10^8\text{cm}} \right)^{1.85}} \\ &= 71\text{cm}^2\text{V}^{-1}\text{s}^{-1}\end{aligned}$$

Solution 3.2

a) $E_{\text{cn}}L_{\text{n}} = 6 \cdot 10^4 \text{Vcm}^{-1}(0.2\mu\text{m}) \approx 1.2\text{V}$ and $E_{\text{cp}}L_{\text{p}} = 24 \cdot 10^4 \text{Vcm}^{-1}(0.2\mu\text{m}) \approx 4.8\text{V}$

$$\begin{aligned} \text{NMOS : } V_{\text{Dsat}} &= \frac{(V_{\text{GS}} - V_{\text{TN}})(E_{\text{cn}}L)}{(V_{\text{GS}} - V_{\text{TN}} + E_{\text{cn}}L)} \\ &= \frac{(1.8\text{V} - 0.5\text{V})(1.2\text{V})}{(1.8\text{V} - 0.5\text{V} + 1.2\text{V})} \approx 0.6\text{V} \end{aligned}$$

$$\begin{aligned} \text{PMOS : } V_{\text{Dsat}} &= \frac{(V_{\text{SG}} - |V_{\text{TP}}|)(E_{\text{cp}}L)}{(V_{\text{SG}} - |V_{\text{TP}}| + E_{\text{cp}}L)} \\ &= \frac{(1.8\text{V} - 0.5\text{V})(4.8\text{V})}{(1.8\text{V} - 0.5\text{V} + 4.8\text{V})} \approx 1.0\text{V} \end{aligned}$$

b) $E_{\text{cn}}L_{\text{n}} = 6 \cdot 10^4 \text{Vcm}^{-1}(0.1\mu\text{m}) \approx 0.6\text{V}$ and $E_{\text{cp}}L_{\text{p}} = 24 \cdot 10^4 \text{Vcm}^{-1}(0.1\mu\text{m}) \approx 2.4\text{V}$

$$\begin{aligned} \text{NMOS : } V_{\text{Dsat}} &= \frac{(V_{\text{GS}} - V_{\text{TN}})(E_{\text{cn}}L)}{(V_{\text{GS}} - V_{\text{TN}} + E_{\text{cn}}L)} \\ &= \frac{(1.2\text{V} - 0.4\text{V})(0.6\text{V})}{(1.2\text{V} - 0.4\text{V} + 0.6\text{V})} = 0.34\text{V} \end{aligned}$$

$$\begin{aligned} \text{PMOS : } V_{\text{Dsat}} &= \frac{(V_{\text{SG}} - |V_{\text{TP}}|)(E_{\text{cp}}L)}{(V_{\text{SG}} - |V_{\text{TP}}| + E_{\text{cp}}L)} \\ &= \frac{(1.2\text{V} - 0.4\text{V})(2.4\text{V})}{(1.2\text{V} - 0.4\text{V} + 2.4\text{V})} = 0.6\text{V} \end{aligned}$$

c)

$$\begin{aligned} \text{NMOS : } \frac{I_{\text{DS}}}{W} &= v_{\text{sat}}C_{\text{ox}} \cdot \frac{(V_{\text{GS}} - V_{\text{TN}})^2}{(V_{\text{GS}} - V_{\text{TN}} + E_{\text{cn}}L)} \\ &= 12.8\text{A(Vcm)}^{-1} \frac{(1.2\text{V} - 0.4\text{V})^2}{(1.2\text{V} - 0.4\text{V}) + 0.6\text{V}} = 585\mu\text{A}/\mu\text{m} \end{aligned}$$

$$\begin{aligned} \text{PMOS : } \frac{I_{\text{DS}}}{W} &= v_{\text{sat}}C_{\text{ox}} \cdot \frac{(V_{\text{SG}} - |V_{\text{TP}}|)^2}{(V_{\text{SG}} - |V_{\text{TP}}| + E_{\text{cp}}L)} \\ &= 12.8\text{A(Vcm)}^{-1} \frac{(1.2\text{V} - 0.4\text{V})^2}{(1.2\text{V} - 0.4\text{V}) + 2.4\text{V}} = 256\mu\text{A}/\mu\text{m} \end{aligned}$$

$$\frac{I_{\text{DsatN}}}{I_{\text{DsatP}}} = \frac{W_{\text{N}}v_{\text{sat}}C_{\text{ox}}(V_{\text{GS}} - V_{\text{TN}})^2/(V_{\text{GS}} - V_{\text{TN}} + E_{\text{cn}}L_{\text{n}})}{W_{\text{P}}v_{\text{sat}}C_{\text{ox}}(V_{\text{SG}} - |V_{\text{TP}}|)^2/(V_{\text{SG}} - |V_{\text{TP}}| + E_{\text{cp}}L_{\text{p}})} = 2.3$$

Solution 3.3

$V_{DD}=1.2V$, $1X=W/L$ (Device Size Ratio), $W = 100nm$, $L = 100nm$

a) $I_{DS} = f(V_{DS})$

We already know the ratio between 1X devices for NMOS and PMOS transistors:

$$\frac{I_{DsatN}}{I_{DsatP}} = 2.3$$

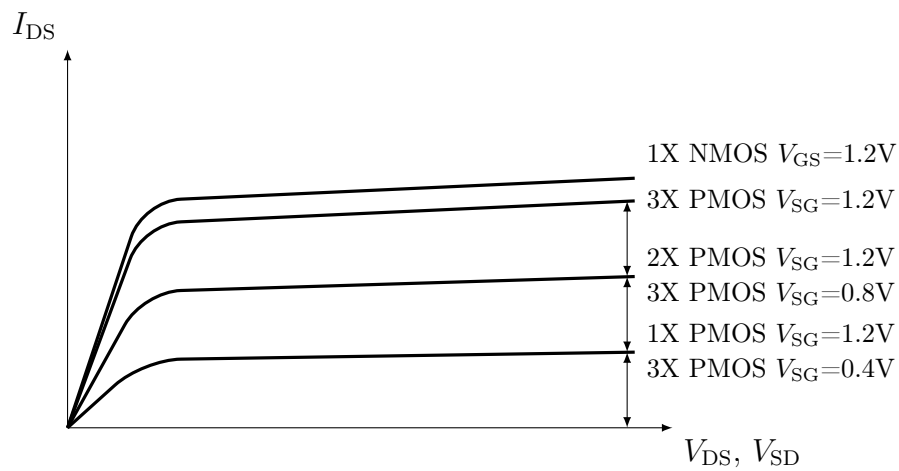


Figure 3.2: Output characteristics of MOS transistors

b) $I_{DS} = f(V_{GS})$

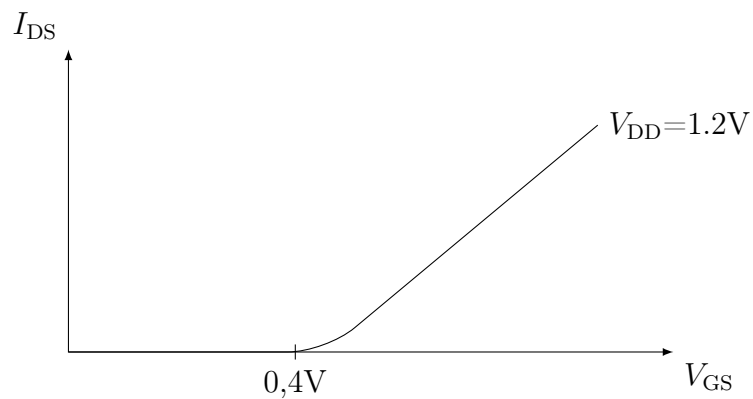


Figure 3.3: Diode characteristic of MOS transistors

Solution 3.4

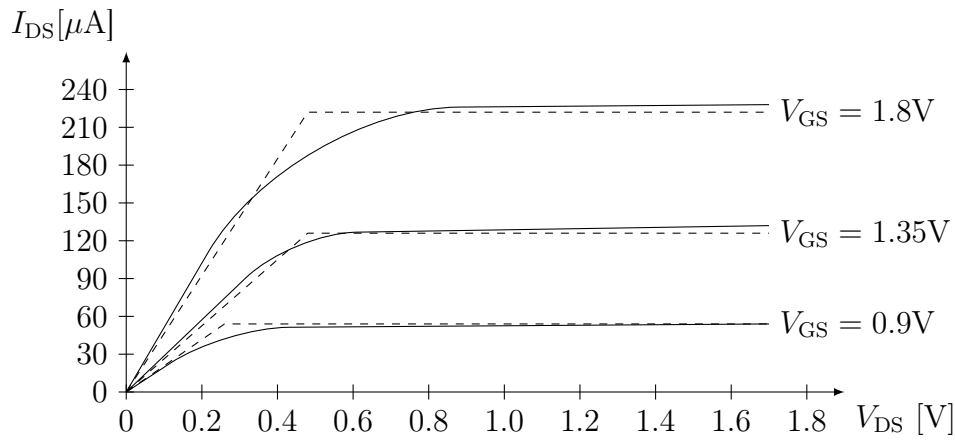


Figure 3.4: I_{DS} versus V_{DS} for NMOS

Using Fig. 3.4 we estimate the saturation value of I_{DS} to $130\mu\text{A}$ at $V_{GS} = 1.35\text{V}$ and to $220\mu\text{A}$ at $V_{GS} = 1.8\text{V}$.

The current equation for each measurement is approximated by

$$I_{DS} = K_S \frac{W}{L} (V_{GS} - V_T)^\alpha \quad (\text{Current equation in the saturation range}).$$

It applies:

$$\frac{220\mu\text{A}}{130\mu\text{A}} = \frac{K_S(1.8\text{V} - 0.5\text{V})^\alpha}{K_S(1.35\text{V} - 0.5\text{V})^\alpha}$$

$$1.69 = 1.53^\alpha$$

$$\log 1.69 = \log 1.53^\alpha$$

$$\log 1.69 = \alpha \cdot \log 1.53$$

$$\alpha = \frac{\log 1.69}{\log 1.53} = 1.25$$

Inserting $\alpha = 1.25$ into the current equation yields

$$130\mu\text{A} = K_S(1.35\text{V} - 0.5\text{V})^{1.25} \Rightarrow K_S = 159 \frac{\mu\text{A}}{\text{V}^{1.25}}$$

$$220\mu\text{A} = K_S(1.8\text{V} - 0.5\text{V})^{1.25} \Rightarrow K_S = 158 \frac{\mu\text{A}}{\text{V}^{1.25}}$$

$$K_S = 160\mu\text{A}/\text{V}^{1.25}$$

Note that the exponent is near 1. For long channel transistors the exponent is more like 2, for short channel transistors more like 1. To check we calculate the current

$$I_{DS} = 160 \frac{\mu\text{A}}{\text{V}^{1.25}} (0.9\text{V} - 0.5\text{V})^{1.25} \approx 50\mu\text{A}$$

This value is close to the expected value in Fig. 3.4.